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INFORMATION DISCLOSURE STATEMENT							1011	JI 04/00/34.		
(Use several sheets if necessary)					APPLICANTS Masahiro SAKURADA et al.					
					FILING DATE December 19, 2005			17 <del>33</del> -		
U.S. PATENT DOCUMENTS										
EXAMINER INITIAL		DOCUMENT NUMBER	DATE		NAME			CLASS	SUB CLASS	
5H.	1)	5,919,302	0706/1999		FALSTER et al.			_		
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FOREIGN PATENT DOCUMENTS										
		DOCUMENT NUMBER		DATE	COUNTRY			CLASS	SUB CLASS	
KH.	2)	JP A 2002-057160 w/ abst. & trans	02/	22/2002	JAPAN	<u> </u>			_	
Fit.	3)	JP A 2000-313691 w/ abst. & trans	11/	14/2000	JAPAN				-	
Fi.H.	4)	JP A 11-147786 w/ abstract & trans	06/	02/1999	JAPAN			_	_	
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OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)										
БH.	5)	Voronkov, "The Mechanism of Swirl Defects Formation in Silicon," Journal of Crystal Growth, Vol. 59, pp. 625-643, 1982								
FH	6)	Dupret et al., "Global Modelling of Heat Transfer in Crystal Growth Furnaces," Int. J. Heat Mass Transfer, Vol. 33, No. 9, pp. 1849-1871, 1990								
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EXAMINER States					DATE CONSIDERED			ERED		
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in										

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